

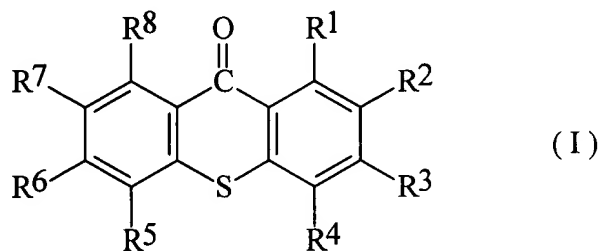
B1  
required. In addition, it is also effective to utilize a compound degradable by alkali, such as an acid generating agent, proposed in JP-A-10-213905, which generates an acid by the action of an alkali-developing solution. Addition of the alkali-degradable compound may contribute to the improvement of pattern profile.

In the Claims:

Please cancel claims 2-5 without prejudice or disclaimer of the subject matter contained therein.

Please amend the claim 1 as follows:

A2  
Sub C1  
1. (Amended) An article comprising a substrate comprising a silicon wafer and a positive resist composition comprising a novolac resin, a radiation-sensitive quinonediazide compound and a (I):



wherein R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup>, R<sup>4</sup>, R<sup>5</sup>, R<sup>6</sup>, R<sup>7</sup>, R<sup>8</sup> independently represent hydrogen, halogen, alkyl, alkoxy, aryl, carboxyl or alkoxycarbonyl